

FORMING A TRANSPARENT WINDOW IN A POLISHING PAD  
FOR A CHEMICAL MECHANICAL POLISHING APPARATUS

ABSTRACT OF THE DISCLOSURE

5 The polishing pad for a chemical mechanical  
polishing apparatus, and a method of making the same. The  
polishing pad has a covering layer with a polishing surface  
and a backing layer which is adjacent to the platen. A  
first opening in the covering layer with a first cross-  
sectional area and a second opening in the backing layer  
10 with a second, different cross-sectional area form an  
aperture through the polishing pad. A substantially  
transparent polyurethane plug is positioned in the aperture,  
and an adhesive material fixes the plug in the aperture.

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